

Amendments to the Claims

This listing of claims will replace all prior versions, and listings, of claims in the application.

Listing of Claims:

- 1 to 29. (Canceled)
30. (Currently Amended) A mixture for depositing an organosilicate film comprising a dielectric constant of 3.5 or below, the mixture comprising at least one structure-former precursor selected from the group consisting of an organosilane and an organosiloxane and a pore-former precursor that is distinct from the at least one structure-former precursor, wherein the pore-former precursor is a hydrocarbon compound consisting of from 1 to 13 carbon atoms and less than or equal to $2n+2$ hydrogen atoms wherein n is the number of carbon atoms having from 1 to 13 carbon atoms, and wherein ~~the~~ at least one of the precursors and/or the organosilicate film exhibits an absorbance in the 200 to 400 nm wavelength range.
31. (Currently Amended) A mixture for depositing an organosilicate film, the mixture comprising: from 5 to 95% by weight of a structure-former precursor selected from the group consisting of an organosilane and an organosiloxane and from 5 to 95% by weight of a pore-former precursor that is distinct from the at least one structure-former precursor, wherein the pore-former precursor is ~~selected from the group consisting of:~~ a hydrocarbon compound consisting of from 1 to 13 carbon atoms and less than or equal to $2n+2$ hydrogen atoms wherein n is the number of carbon atoms having from 1 to 13 carbon atoms, and wherein the at least one of the precursors and/or the organosilicate film exhibits an absorbance in the 200 to 400 nm wavelength range.
- 32 to 37. (Canceled)
38. (Currently Amended) The mixture of claim 30 wherein the hydrocarbon is selected from the group consisting of alpha-terpinene, limonene, cyclohexane, gamma-

terpinene, dimethylhexadiene, ethylbenzene, norbornadiene, ~~cyclopentene oxide~~, 1,2,4-trimethylcyclohexane, 1,5-dimethyl-1,5-cyclooctadiene, camphene, adamantane, 1,3-butadiene, ~~substituted diones~~, alpha-pinene, beta-pinene, and decahydronaphthelene.

39. (Previously Presented) The mixture of claim 30 wherein the porogen is removable by ultraviolet radiation.

40. – 42. (Canceled)

43. (Currently Amended) The mixture of claim 31 wherein the hydrocarbon is selected from the group consisting of alpha-terpinene, limonene, cyclohexane, gamma-terpinene, dimethylhexadiene, ethylbenzene, norbornadiene, ~~cyclopentene oxide~~, 1,2,4-trimethylcyclohexane, 1,5-dimethyl-1,5-cyclooctadiene, camphene, adamantane, 1,3-butadiene, ~~substituted diones~~, alpha-pinene, beta-pinene, and decahydronaphthelene.

44. (Previously Presented) The mixture of claim 31 wherein the porogen is removable by ultraviolet radiation.

45. – 47. (Canceled)

48. (Previously Presented) The mixture of claim 30 wherein the organosilicate film is represented by the formula $\text{Si}_v\text{O}_w\text{C}_x\text{H}_y\text{F}_z$, where $v+w+x+y+z = 100\%$, v is from 10 to 35 atomic%, w is from 10 to 65 atomic%, x is from 5 to 30 atomic%, y is from 10 to 50 atomic%, and z is from 0 to 15 atomic%.

49. (Previously Presented) The mixture of claim 30 wherein the at least one structure-former precursor comprises an organosilane.

50. (Currently Amended) The mixture of claim 49 wherein the organosilane is selected from the group consisting of: methylsilane, dimethylsilane, trimethylsilane, tetramethylsilane, phenylsilane, methylphenylsilane, cyclohexylsilane, tert-butylsilane, ethylsilane, diethylsilane, tetraethoxysilane, dimethyldiethoxysilane, dimethyldimethoxysilane, dimethylethoxysilane, methyl-diethoxysilane, triethoxysilane, methyltriethoxysilane, trimethylphenoxysilane, phenoxysilane, ditert-butylsilane, diethoxysilane, diacetoxymethylsilane, ~~methyltriethoxysilane~~, di-tert-butylsilane, and mixtures thereof.
51. (Previously Presented) The mixture of claim 30 wherein the at least one structure-former precursor comprises an organosiloxane.
52. (Previously Presented) The mixture of claim 51 wherein the organosiloxane is selected from the group consisting of: 1,3,5,7-tetramethylcyclotetrasiloxane, octamethylcyclotetrasiloxane, hexamethylcyclotrisiloxane, hexamethyldisiloxane, 1,1,2,2-tetramethyldisiloxane, octamethyltrisiloxane, and mixtures thereof.
53. (Previously Presented) The mixture of claim 30 wherein the organosilane comprises diethoxymethylsilane.
54. (Currently Amended) The mixture of claim 53 wherein the hydrocarbon is selected from the group consisting of alpha-terpinene, limonene, cyclohexane, gamma-terpinene, dimethylhexadiene, ethylbenzene, norbornadiene, ~~cyclopentene oxide~~, 1,2,4-trimethylcyclohexane, 1,5-dimethyl-1,5-cyclooctadiene, camphene, adamantane, 1,3-butadiene, ~~substituted dienes~~, alpha-pinene, beta-pinene, and decahydronaphthalene.
55. (Previously Presented) The mixture of claim 31 wherein the organosilicate film is represented by the formula $\text{Si}_v\text{O}_w\text{C}_x\text{H}_y\text{F}_z$, where $v+w+x+y+z = 100\%$, v is from 10 to

35 atomic%, w is from 10 to 65 atomic%, x is from 5 to 30 atomic%, y is from 10 to 50 atomic%, and z is from 0 to 15 atomic%.

56. (Previously Presented) The mixture of claim 31 wherein the at least one structure-former precursor comprises an organosilane.
57. (Currently Amended) The mixture of claim 56 wherein the organosilane is selected from the group consisting of: methylsilane, dimethylsilane, trimethylsilane, tetramethylsilane, phenylsilane, methylphenylsilane, cyclohexylsilane, tert-butylsilane, ethylsilane, diethylsilane, tetraethoxysilane, dimethyldiethoxysilane, dimethyldimethoxysilane, dimethylethoxysilane, methyl-diethoxysilane, triethoxysilane, methyltriethoxysilane, trimethylphenoxysilane, phenoxysilane, ditertbutylsilane, diethoxysilane, diacetoxymethylsilane, ~~methyltriethoxysilane~~, di-tert-butylsilane, and mixtures thereof.
58. (Previously Presented) The mixture of claim 31 wherein the at least one structure-former precursor comprises an organosiloxane.
59. (Previously Presented) The mixture of claim 58 wherein the organosiloxane is selected from the group consisting of: 1,3,5,7-tetramethylcyclotetrasiloxane, octamethylcyclotetrasiloxane, hexamethylcyclotrisiloxane, hexamethyldisiloxane, 1,1,2,2-tetramethyldisiloxane, octamethyltrisiloxane, and mixtures thereof.
60. (Previously Presented) The mixture of claim 31 wherein the organosilane comprises diethoxymethylsilane.
61. (Currently Amended) The mixture of claim 60 wherein the hydrocarbon is selected from the group consisting of alpha-terpinene, limonene, cyclohexane, gamma-terpinene, dimethylhexadiene, ethylbenzene, norbornadiene, ~~cyclopentene-oxide~~,

1,2,4-trimethylcyclohexane, 1,5-dimethyl-1,5-cyclooctadiene, camphene, adamantane, 1,3-butadiene, substituted dienes, alpha-pinene, beta-pinene, and decahydronaphthelene.